

[1].

[2].

«Surface and coating technology», «Thin solid films»

[3].

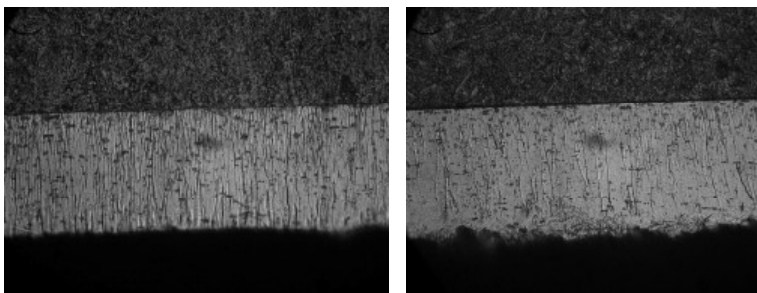
80%.

(CrC, TiC CrN, TiN, Cr, Ti[C,N]),

3

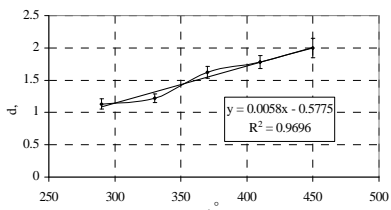
			60		50		-
			290	450°			-
					[4].		-
		$2 \cdot 10^{-5}$	110				-
		~50					-
				870°	38 3		-
						400°	-
							-
5		10			1		-
		Neophot-30.					-
		-3					-
	136°		20				-
		9450-76.					-
		9454-78			PSW-30		U-
		-1.					-
					102-02.		-
			-2,0	CuK			-
)						(.1,	-
					1,13	2 (.2).	-
410°		241 / ²	184 / ² ,			290	-
		450°			225 / ² (.3).		-
					-		-
	«	220 / ²	».	241 / ²	281 / ² .	290° ,	-
							-
		1,5					-

$0,53 / ^2$
 330°
 $0,98 / ^2$
 $9,4 /$ $8,68 /$
 $0,67 / ^2$ 330° 370°
 $8,68$ $9,45 /$
 $0,76 / ^2$ 450°
 $(\dots 4)$ $9,29 /$

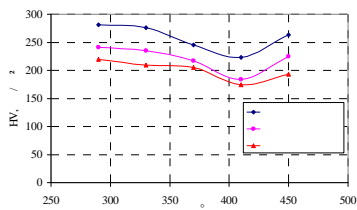


1.

, $\times 1000 \times 0,3$ - 290° ; - 450°



2.

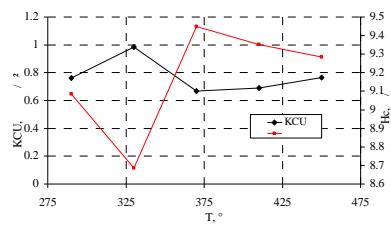


3.

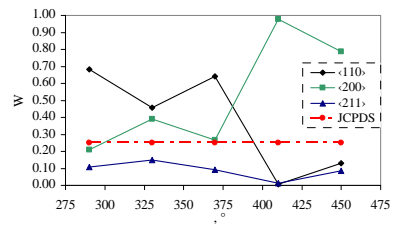
$2\theta = 20 \dots 100^\circ$
 $(110), (200), (211)$

(200).
 <110>. . 5.
 <200>.
 <200>.

(110)
 [5].
 290°
 330 370°
 <110>,
 410 450°



4.



5.

38 3

[4].

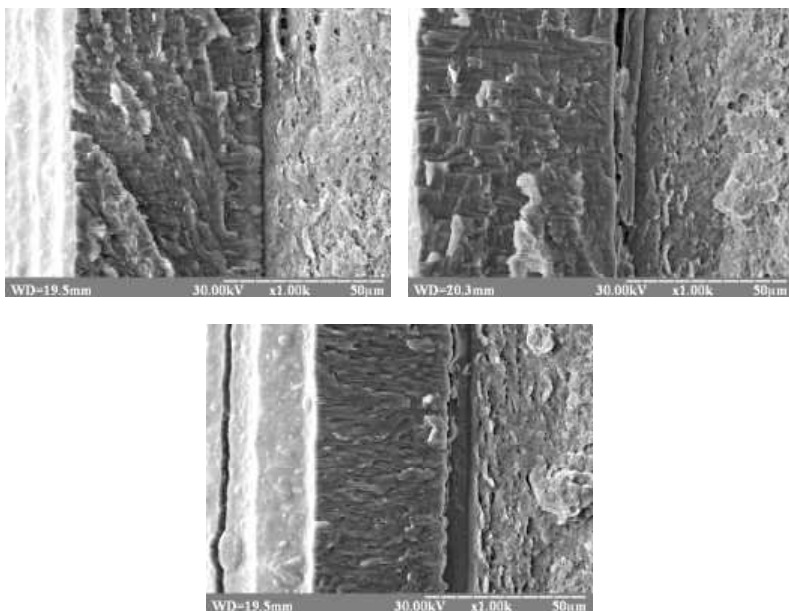
[6].

290...410°
 450°

(~ 0,2%).

$\sim 5 \cdot 10^{10} \text{ }^{-2}$,

[7]



. 5.

,
 : -290° , -370° , -450°
 « - » ,
 , , ,
 , , ,
 ,
 290° , (. 5).
 ,
 (5) , 370° ,

290° .

450° (5).

[8],

(450°).

(450°)

410° .

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